

Fabrication of nanowire using ash trimming technique

Abstract

The paper present a report on fabrication of Nanowire using plasma oxidation, we monitor changes by studying the morphology and $\Delta w/\Delta h$, the study also revealed that the proposed fabrication method could potentially be used to fabricate specific nanometer-scale structure and space structure with uniform surface morphology without any damage to the photoresist. Yet with reduced ashing time and without popping of the photoresist ashing process when the a fabricated is being carried out and subsequently trimmed to nano size by plasma oxidation, the study also revealed the dramatic increase in aspect ratio as the structure reduces in lateral dimension.